AMENDMENTS TO THE CLAIMS

1-22. (Canceled).

23. (Currently Amended): An article comprising a non-conductive glass substrate with at least one continuous metal layer based on tungsten or molybdenum deposited directly thereon, and a copper or silver layer at least partially covering the tungsten or molybdenum layer and in direct contact with the tungsten and molybdenum layer, wherein the thickness of the tungsten or molybdenum layer is between 30 nm and 500 nm and wherein the metal layer is deposited by a process which comprises:

providing at least one tungsten- or molybdenum-containing precursor in the form of a metal halide or an organometallic compound and at least one reducing agent; and

forming the at least one metal layer from the tungsten- or molybdenum-containing precursor and the at least one reducing agent by chemical vapor deposition.

24. (Canceled).

25. (Previously Presented): The article of claim 23, further comprising at least partially covering the copper or silver layer with at least one protective layer containing at least one metal chosen from the group consisting of nickel, chromium, titanium, tantalum, niobium, palladium, and zirconium.

26. (Previously Presented): The article of claim 23, wherein the thickness of the tungsten or molybdenum layer is between 70 nm and 500 nm.

27. (Previously Presented): The article of claim 23, wherein the thickness of the copper or silver layer is between 0.1 μm and 10 μm.

28. (Previously Presented): The article of claim 25, wherein at least one of the layers is etched or deposited in a discontinuous manner.

29. (Currently Amended): An article comprising a non-conductive glass substrate with at least one continuous metal layer based on tungsten or molybdenum deposited directly

thereon, and a copper or silver layer at least partially covering the tungsten or molybdenum layer and in direct contact with the tungsten and molybdenum layer, wherein the thickness of the tungsten or molybdenum layer is between 30 nm and 500 nm.

30. (Canceled).

31. (Previously Presented): The article of claim 29, further comprising at least partially covering the copper or silver layer with at least one protective layer containing at least one metal chosen from the group consisting of nickel, chromium, titanium, tantalum, niobium, palladium, and zirconium.

32. (Previously Presented): The article of claim 29, wherein the thickness of the tungsten or molybdenum layer is between 70 nm and 500 nm.

33. (Previously Presented): The article of claim 29, wherein the thickness of the copper or silver layer is between 0.1 μm and 10 μm.

34. (Previously Presented): The article of claim 31, wherein at least one of the layers is etched or deposited in a discontinuous manner.

35. (Currently Amended): Float glass comprising a non-conductive glass substrate with at least one continuous metal layer based on tungsten or molybdenum deposited directly thereon, and a copper or silver layer at least partially covering the tungsten or molybdenum layer and in direct contact with the tungsten and molybdenum layer, wherein the thickness of the tungsten or molybdenum layer is between 30 nm and 500 nm.

36. (Previously Presented): The float glass of claim 35, wherein the metal layer is deposited by a process which comprises:

providing at least one tungsten- or molybdenum-containing precursor in the form of a metal halide or an organometallic compound and at least one reducing agent; and

forming the at least one metal layer from the tungsten- or molybdenum-containing precursor and the at least one reducing agent by chemical vapor deposition.

37. (Previously Presented): The float glass of claim 36, further comprising at least partially covering the copper or silver layer with at least one protective layer containing at least one metal chosen from the group consisting of nickel, chromium, titanium, tantalum, niobium, palladium, and zirconium.

38. (Previously Presented): The float glass of claim 36, wherein the thickness of the tungsten or molybdenum layer is between 70 nm and 500 nm.

39. (Previously Presented): The float glass of claim 36, wherein the thickness of the copper or silver layer is between 0.1 μm and 10 μm.

40. (Previously Presented): The float glass of claim 36, wherein at least one of the layers is etched or deposited in a discontinuous manner.

41. (Previously Presented): The float glass of claim 36, in the form of a ribbon.

42. (Previously Presented): The float glass of claim 36, in the form of a glazing.

43. (Previously Presented): The float glass of claim 36, in the form of a mirror.